IN THE UNITED STATES PATENT AND TO DEMARK OFFICE

In re Application of:

Wilbur Catabay et. al.

Serial No.:

09/884,736

Filed:

June 19, 2001

For:

In-Situ Plasma Treatment of Low-k films to generate a non-homogenous

film for use as an etch stop and or

Hardmask in Damascene structures

DEC 2 6 2277 JULY

Group Art Unit:

Examiner:

Atty Docket:

/ 00-654

I hereby certify that this correspondence is being deposited with the U.S. Postal Service as First Class Mail in an envelope addressed to: Assitant Commissioner for Patents, Washington D.C. 20231, on the date indicated below:

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Signature

INFORMATION DISCLOSURE STATEMENT

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Assistant Commissioner for Patents Washington, D.C. 20231

Dear Sir:

The references listed in the attached form, copies of which are attached, may be material to examination of above-identified application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR 1.56 and 1.97.

It is requested that the information disclosed herein be made of record in the application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

If it is determined that any additional fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 12-2252.

Respectfully submitted,

LSI Logic Corporation 1551 McCarthy Blvd., MS D-106 Milipitas, CA 95035

Date: 12/18/01

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Reg. No. 39,136

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